

REMARKS

Counsel thanks Primary Examiner D. Coleman and Examiner K. Nguyen for the courtesy of the interview held on August 12, 2004.

At the Interview, the Examiners have agreed that independent claims 5 and 14 define over the applied art of record, especially *Coffman* (U.S. Patent No. 6,451,627), because the reference fails to teach or suggest the claimed steps of forming a photoresist layer and a metal layer as detailed in the Interview Summary.

The art rejections manifested in the outstanding Office Action are therefore traversed and should be withdrawn.

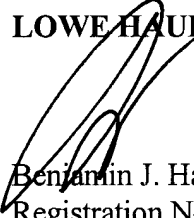
Indication of allowable subject matter of the pending claims in the absence of other relevant art is believed appropriate and therefore courteously solicited.

The Examiner is invited to telephone the undersigned, Applicant's attorney of record, to facilitate advancement of the present application.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 07-1337 and please credit any excess fees to such deposit account.

Respectfully submitted,

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Date: August 13, 2004